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Sagehashi et al.

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(54) **MONOMER, POLYMER, RESIST
COMPOSITION, AND PATTERNING
PROCESS**

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(58) **Field of Classification Search**

None

See application file for complete search history.

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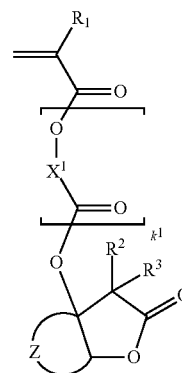
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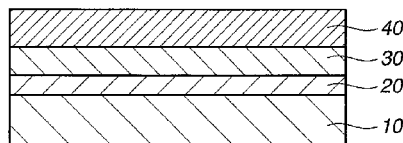
(57) **ABSTRACT**

A polymer for resist use is obtainable from a monomer having
formula (1) wherein R^1 is H, CH_3 or CF_3 , R^2 and R^3 each are
H or a monovalent hydrocarbon group, X^1 is a divalent hydro-
carbon group, $k^1=0$ or 1, and Z forms a 5 or 6-membered
alicyclic ring. A resist composition comprising the polymer is
shelf stable and displays a high dissolution contrast, con-
trolled acid diffusion and low roughness during both alkaline
development and organic solvent development.



17 Claims, 1 Drawing Sheet

PHOTORESIST COATING



PHOTORESIST EXPOSURE

